IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

n re Application of:

Hashim, et al.

Serial No.:

09/138,429

Filed:

August 24, 1998

For:

 $oldsymbol{\omega}$ Collimated and Long Throw Magnetron Sputtering of Nickel/Iron Films for Magnetic **Recording Head Applications** 

**BOX AF** 

**Assistant Commissioner for Patents** Washington, D.C. 20231

Dear Sir:

**Group Art Unit:** 

1753

Examiner:

Mercado, J.

Confirmation No.:

4066

CERTIFICATE OF MAILING 37 C.F.R. 1.8

I hereby certify that this correspondence is being deposited or June 11, 2001, with the U. S. Postal Service as First Class Mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, D.C. 20231.

Signature

## **RESPONSE TO FINAL OFFICE ACTION DATED APRIL 9, 2001**

In response to the Final Office Action dated April 9, 2001, having a shortened statutory period for response set to expire on June 9, 2001, Applicants request reconsideration of the claims pending in the application for reasons discussed below. The Commissioner is authorized to charge Deposit Account 0782/AMAT/2406.X1/NAN for any fees required in conjunction with this response.

## **PENDING CLAIMS:**

1. An apparatus for depositing a magnetic film, comprising:

a sputtering chamber containing a target, a substrate support having a surface that is separated from the target, and a grounded collimator positioned between the target and the substrate support; and

an annular magnet array disposed within the chamber to form a magnetic field that is substantially parallel to the surface of the substrate support, the annular magnet array being concentrically positioned about the surface of the substrate support.